Model P140
14mm Rotary Potentiometer
Dual Unit
Conductive Plastic Element
With / Without Bushing
Insulated Shaft
RoHS Compliant



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Side Adjust, without Bushing	P140KV
Side Adjust, with Bushing	P140KV1
Top Adjust, without Bushing	P140KH
Top Adjust, with Bushing	P140KH1

ELECTRICAL¹

Resistance Range, Ohms	500-2M (for "B" taper) 1K-2M (for other tapers)
Standard Resistance Tolerance	± 20%
Residual Resistance	20 ohms max.
Input Voltage, maximum	50 Vac max.
Power rating, Watts	0.05w
Dielectric Strength	500Vac, I minute
Insulation Resistance, Minimum	100M ohms at 250Vdc
Sliding Noise	100mV max.
Gang Error (Multi-ganged)	-40dB - 0dB, ±3dB
Actual Electrical Travel, Nominal	260°

MECHANICAL

Total Mechanical Travel	300°± 10°
Static Stop Strength	70 oz-in
Rotational Torque	0.5 to 1.25 oz-in
	0.5 to 1.25 o

ENVIRONMENTAL

Operating Temperature Range	-20°C to +70°C
Rotational Life	30,000 cycles

¹ Specifications subject to change without notice.

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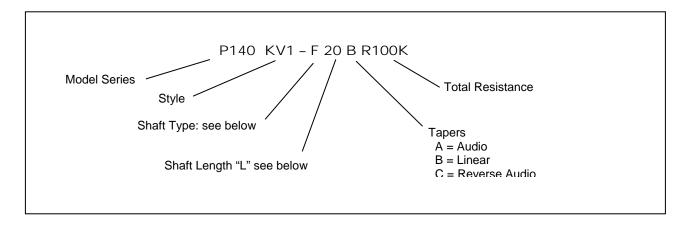
4200 Bonita Place, Fullerton, CA 92835 USA

Phone: 714 447 2345 Website: www.bitechnologies.com

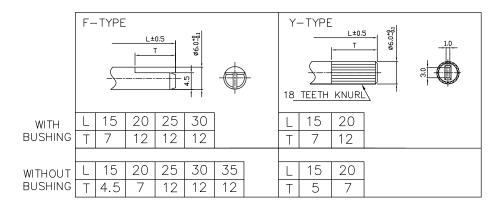
electronics
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ORDERING INFORMATION²



Shaft Types



STANDARD RESISTANCE VALUES, OHMS

500	1 K	2K	5K	10K	20K	50K	100K	200K	500K	1MFG

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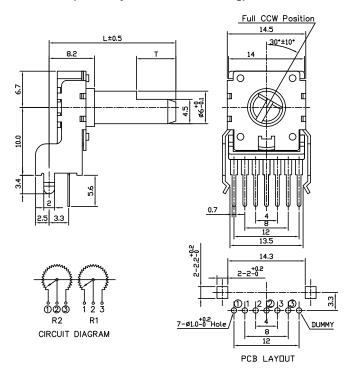


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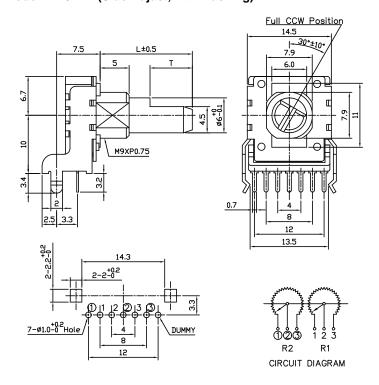
² Contact our customer service for custom designs and features.

OUTLINE DRAWING

Model P140KV (Side Adjust, without Bushing)



Model P140KV1 (Side Adjust, with Bushing)



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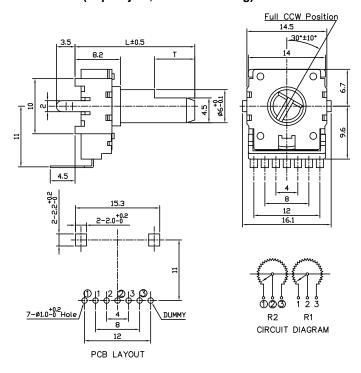
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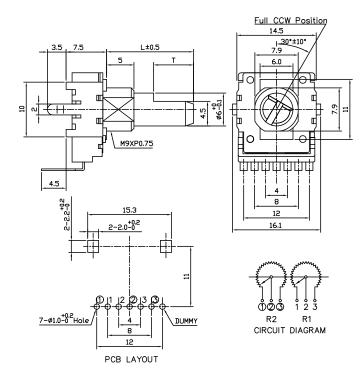
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Model P140

Model P140KH (Top Adjust, without Bushing)



Model P140KH1 (Top Adjust, with Bushing)





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